

IN THE CLAIMS

Kindly amend the claim 2, and cancel claims 1, 6, 8, so that the claims appear as set forth hereto, all without prejudice.

1. (Cancelled) A method for the manufacture of microstructures (18) in substrates (24), comprising using a combination of photolithographic mask technology and micro contact printing, wherein said microstructure has an aspect ratio in a range of 1:5 to 1:20.
2. (Presently Amended) A method for the manufacture of microstructures in substrates, comprising the steps of
 - a) providing a process mask (10);
 - b) creating soft stamps (16) from a master comprising a microstructure (18) having an aspect ratio in a range of 1:5 to 1:20, said step of creating including creating holding blocks (20, 22) attached to said microstructure (18), each of said holding blocks having an aspect ratio in a range of 1:1 to 1:2 so as to stabilize said microstructure (18) mechanically;
 - c) attaching said soft stamps (16) to said mask (10);
 - d) stamping a desired pattern into a resist layer (26) provided on a substrate (24) to be processed; and
 - e) curing said pattern with UV light.
3. (Original) The method according to claim 2, wherein said mask (10) comprises a plating compensation area.
4. (Previously Amended) The method according to claim 3, wherein said plating compensation area is covered with a metallic layer (12).

5. (Original) The method according to claim 4, wherein said metal is chromium.
6. (Cancelled) The method according to claim 2, wherein said microstructure (18) is mechanically stabilized by greater holding blocks (20, 22) attached to said microstructure (18).
7. (Previously Cancelled)
8. (Cancelled) A P2 structure for a magnetic recording head, said structure being manufactured according to the method of claim 2.